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**Abstract**

The invention relates to a process for controlling an installation for plasma treatment of workpieces. The installation has a constant voltage source for producing a glow discharge voltage V, which includes a control unit for controlling the magnitude of the glow discharge voltage V and a switch unit which can periodically switch off the glow discharge voltage V in various pulse-pause ratios. The installation also has a sensor for measuring the temperature of the workpiece, which is connected to the control unit so that the glow discharge voltage V is increased if the measured temperature is less than a given treatment temperature and decreased if the measured temperature is greater than the treatment temperature. The glow discharge voltage V is monitored so that if it falls below a lower threshold value the pulse-pause ratio of the glow discharge voltage V is reduced and if it exceeds an upper threshold value the pulse-pause ratio is increased.

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